ABSTRACT

PROCESS FOR FORMING METAL DEPOSITED FILM CONTAINING ALUMINUM AS MAIN COMPONENT BY USE OF ALKYL ALUMINUM HYDRIDE

A process for forming an additive-containing Al film of good quality according to the CVD method utilizing an alkyl aluminum hydride, a gas containing an additive and hydrogen, which is an excellent deposited film formation process also capable of selective deposition of additive-containing Al.

FIGURE 3A - 3E